

National Institute of Technology, Delhi

Name of the Examination: B. Tech: END Semester Examination: Delayed Autumn 2022

Branch	: ECE	Semester	: I
Title of the Course	: Basics of Electronics and Electrical Engineering	Course Code	: ECBB 101

Time: 3 Hours

Maximum Marks: 50

- Questions are printed on BOTH sides. Answers should be CLEAR AND TO THE POINT.
- All parts of a single question must be answered together. ELSE QUESTIONS SHALL NOT BE EVALUATED.

Use following data if not given in a problem: $\epsilon_o = 8.85 \times 10^{-14} \text{F/cm}$, $\epsilon_r (\text{SiO}_2) = 3.9$, $\epsilon_r (\text{Si}) = 11.8$, At room temperature for Si [$\mu_n = 1350 \text{cm}^2/\text{V}\cdot\text{S}$, $\mu_p = 480 \text{cm}^2/\text{V}\cdot\text{S}$, $n_i = 1.5 \times 10^{10}/\text{cm}^3$, $E_g = 1.12 \text{eV}$], $k = 8.62 \times 10^{-5} \text{eV/K}$, $\tau_n = \tau_p = 1 \mu\text{s}$, $E_g (\text{Ge}) = 0.7 \text{eV}$, $n_i (\text{Ge}) = 2.5 \times 10^{13}/\text{cm}^3$. Assume $KT = 0.026 \text{V}$

1. (a) A doped Si sample A of thickness 3mm, shows a hall voltage of $V_y = 5 \text{mV}$ for current density $J_x = 500 \text{Amp/m}^2$ under a magnetic field of $B_z = 1 \text{Wb/m}^2$. [3+2+1]
 - (i) Find the type of the semiconductor sample A.
 - (ii) Doping concentration of the semiconductor sample A.
 - (iii) Sketch and label the energy band diagram of the semiconductor sample A.
- (b) If another Si sample B, of the same physical dimension, is tested under the same current density, magnetic field, and the Hall Voltage applied with same magnitude, but opposite polarity, then
 - (i) Sketch the energy band diagram of the sample B.
 - (ii) Mention the Type of the Semiconductor sample B.
- (c) Now sketch and label the combined energy band diagram for samples A and B, (if samples A and B are joined together to make a pn junction), which are at atomic contact levels grown on Single crystal at thermal equilibrium.
2. A Si sample is doped with acceptor impurity of the given profile $N_A = 10^{14} \cdot \exp(-ax^2)$. For $x \geq 0$ assume $a = 2/(\mu\text{m})^{1/2}$ [4]
 - (a) Find the expression and value for the electric field at $x = a/2$.
 - (b) Find the expression and value for the electric field at $x = a$.
3. The current equation for a p-n junction for $V > \frac{3KT}{q}$ is given as $I = I_0 \cdot \exp\left[\frac{q \cdot V}{kT}\right]$ [3]

Where, $I_0 = A \cdot \exp\left[\frac{-1.12 \text{eV}}{kT}\right]$.

Calculate the suitable forward bias voltage required at 320°K for this diode to maintain the same current as available in this diode at 300°K for 0.5 V of forward Bias.

4. Consider an uniformly doped GaAs junction at $T=300^\circ K$, at Zero bias only 20% of the total space charge region/depletion region is to be in the p-region. The contact potential $V_0 = 1.20V$ for Zero bias determine [3]

(a) Acceptor concentration (N_A) and (b) Donor concentration (N_D).

Assume, $n_i = 1.8 \times 10^{16}/cm^3$.

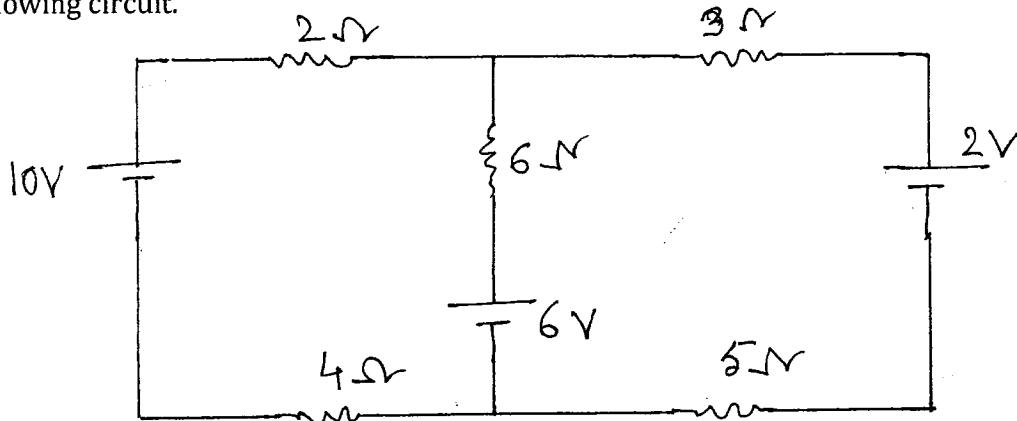
5. Consider a Si p-n Junction at $T = 300^\circ K$ with a p-type doping concentration of $N_A = 10^{18}/cm^3$. Determine the n-type doping concentration such that the maximum electric field is $|E_{max}| = 3 \times 10^5 V/cm$ at reverse bias of 25V. [3]

6. Determine the equilibrium carrier concentrations, n_0 and p_0 for a Si sample at $T=300^\circ K$ [3], if the fermi energy is 0.22eV above the valance band energy.

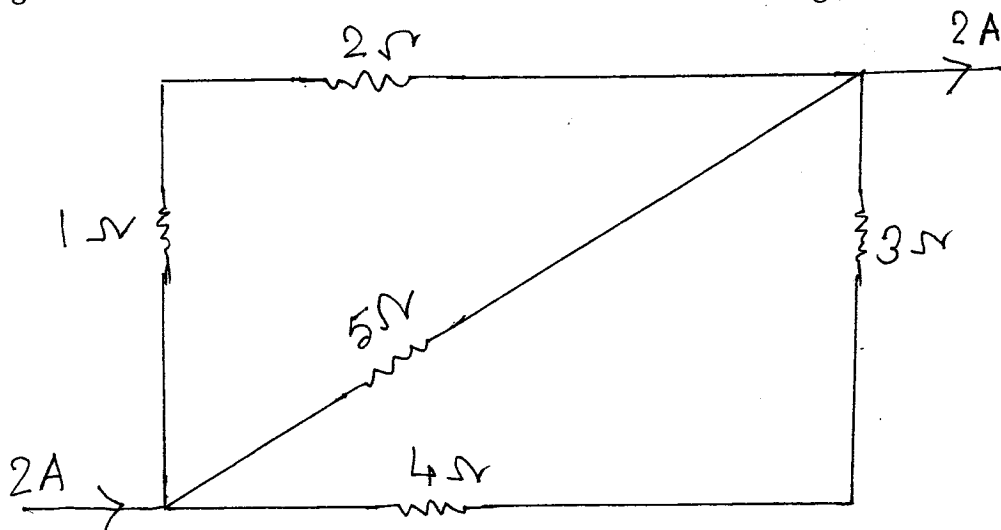
Given: $N_c = 2.8 \times 10^{19}/cm^3$, $N_v = 1.04 \times 10^{19}/cm^3$, $E_g|_{Si} = 1.12eV$ at $T=300^\circ K$.

7. Si is doped with B to the concentration of $4 \times 10^{17} atoms/cm^3$. Assume $n_i = 1.5 \times 10^{10}/cm^3$ and $\frac{KT}{q} = 25mV$ at $300^\circ K$, then what will be the shift in E_F compared with undoped Si? [3]

8. Using mesh current method calculate the current flowing in the resistor 6Ω in the following circuit. [2]







9. Using KCL and KVL calculate all the branch current in the following circuit. [4]



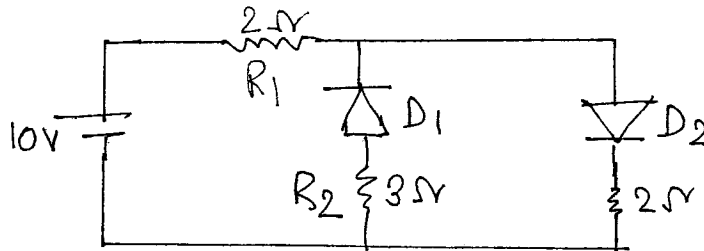
10. For a Si Bar having the length of $4\mu\text{m}$, doped n-type at $10^{17}/\text{cm}^3$. Calculate the current [4]
for an applied voltage of 2V having a cross-sectional area of 0.01cm^2 . If the voltage is
now raised at 1000V, then what will be the change in current? Electron and hole
Mobilities are $1350\text{ cm}^2/\text{V} - \text{sec}$ and $400\text{ cm}^2/\text{V} - \text{sec}$, respectively for the low electric
field. For higher field, the saturation velocity is 10^7 cm/sec .
11. Consider two energy level E_1 , E_2 above E_F and E_2 below E_F in a semiconductor [2]
material. P_1 and P_2 are respectively the probabilities of E_1 being occupied by an electron
and E_2 being empty. Then which one of following option will be correct, prove with
proper calculations (*without proving through calculations answer is not acceptable*).
- (a) $P_1 > P_2$.
(b) $P_1 = P_2$
(c) $P_1 < P_2$.

12.	<p>Please choose/ fill up the correct answer against the question and write only the appropriate answer in your answer sheet.</p> <p>(a) For a FB diode, the contact potential _____, as temperature increase. (i) Decreases (ii) Remains Constant (iii) Increases.</p> <p>(b) The "Wide end Arrow" in the schematic symbol of a pn junction diode indicates_____. (i) Ground (ii) Direction of Electron Flow (iii) Cathode (iv) Anode.</p> <p>(c) Which statement best describes a "Real Insulator." (i) A material with many free electrons (ii) A material doped to have some free electrons (iii) A material with few free electrons (iv) No description fits.</p> <p>(d) Effectively how many valence electrons are there in each atom within a Si crystal? (i) 2 (ii) 4 (iii) 8 (iv) 16.</p> <p>(e) What factor(s) does the barrier potential of a pn junction diode depend on: (i) Type of semiconductor material (ii) The amount of doping (iii) The temperature (iv) All the above (v) Type of semiconductor material, doping but not temperature.</p> <p>(f) Which one of the following represents forward bias circuit?</p>	[1+1+1+2+2+2+2+2]
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- (i) $0V$ —  — R — $-2V$
- (ii) $-4V$ —  — R — $-3V$
- (iii) $-2V$ —  — R — $+2V$
- (iv) $-3V$ —  — R — $+5V$

(g) The given circuit has two ideal diodes connected as shown in the figure below. The current flowing through the resistance R_1 will be:

- (i) 2.5 A (ii) 10.0 A (iii) 1.43 A (iv) 3.13 A.



(h) Pure Si at 500K has equal no. of electron and hole concentrations of $1.5 \times 10^6 / m^3$. Doping by Indium (In) increases the hole concentration to $4.5 \times 10^{22} / m^3$. The type of the doped semiconductor will be:

- (i) n-type with electron concentration $5 \times 10^{22} / m^3$. (ii) p-type with electron concentration $2.5 \times 10^{23} / m^3$ (iii) n-type with electron concentration $2.5 \times 10^{10} / m^3$ (iv) p-type with electron concentration $5 \times 10^9 / m^3$.

Useful Equations

$$\epsilon_r = \frac{\epsilon(\omega)}{\epsilon_0}$$

$$\epsilon_x = \frac{-V}{x-x_0} = \frac{-V}{d}; d = (x-x_0)$$

$$f \sim \frac{W_2 - W_1}{h}$$

$$\lambda = \frac{h}{mv} = \frac{h}{p} = \frac{1.24}{E_g \text{ (eV)}} \mu\text{m}$$

$$n = p = n_i \propto \exp \left[-\frac{E_g}{2kT} \right]$$

$$J_{p, drift} = q \cdot p \cdot v_{dp}$$

$$\frac{I}{A} = \sigma \left(\frac{V}{L} \right) \text{ or } V = \left(\frac{L}{\sigma A} \right) \cdot I = \left(\frac{\rho L}{A} \right) \cdot I = I \cdot R$$

$$p_0 = \int_{E_c}^{\infty} [1 - f(E)] \cdot N(E) dE = N_V \cdot \exp \left[\frac{-(E_F - E_V)}{kT} \right]$$

$$\text{Continuity: } \frac{\partial p(x, t)}{\partial t} = \frac{\partial \delta p}{\partial t} = -\frac{1}{q} \frac{\partial J_p}{\partial x} - \frac{\delta p}{\tau_p} \quad \frac{\partial \delta n}{\partial t} = \frac{1}{q} \frac{\partial J_n}{\partial x} - \frac{\delta n}{\tau_n}$$

$$p_i = N_V \cdot \exp \left[\frac{-(E_i - E_V)}{kT} \right]$$

$$V = \frac{J}{q \cdot p_0} \cdot B \cdot t$$

$$V_0 = kT \cdot \ln \left(\frac{N_A \cdot N_B}{n_i^2} \right)$$

$$I = q \cdot A \cdot \left[\frac{D_p}{L_p} \cdot p_n + \frac{D_n}{L_n} \cdot n_p \right] \cdot \left[\exp \left(\frac{qV}{kT} \right) - 1 \right]$$

$$\text{For steady state diffusion: } \frac{d^2 \delta n}{dx^2} = \frac{\delta n}{D_n \tau_n} = \frac{\delta n}{L_n^2} \quad \frac{d^2 \delta p}{dx^2} = \frac{\delta p}{L_p^2}$$

$$V \equiv \int_{x_0}^x \epsilon_x dx$$

$$J = \frac{N \cdot q \cdot v}{L \cdot A} = N \cdot q \cdot V \text{ (volume)} \\ = \rho \text{ (Charge Density)} \cdot V$$

$$\lambda = h/mv = h/p, \text{ where } p = mv$$

$$E = \frac{1}{2} m \cdot v^2 = \frac{p^2}{2m} = \frac{\hbar^2}{2m} k^2, \text{ since } p = \hbar \cdot k$$

$$f(E) = \frac{1}{1 + \exp \frac{(E - E_F)}{kT}}$$

$$J_{drift} = J_{p, drift} + J_{n, drift} = q \cdot [\mu_n \cdot n + \mu_p \cdot p] \cdot E$$

$$n_0 = \int_{E_c}^{\infty} f(E) N(E) dE = N_C \cdot \exp \left[\frac{-(E_c - E_F)}{kT} \right]$$

$$N_C = 2 \cdot \left[\frac{2 \pi m_n^* kT}{h^2} \right]^{3/2}; N_V = 2 \cdot \left[\frac{2 \pi m_p^* kT}{h^2} \right]^{3/2}$$

$$n_i = N_C \cdot \exp \left[\frac{-(E_c - E_i)}{kT} \right]$$

$$n_0 = N_C \cdot \exp \left[\frac{-(E_c - E_F)}{kT} \right]; p_0 = N_V \cdot \exp \left[\frac{-(E_F - E_V)}{kT} \right]$$

$$\text{Diffusion length: } L = \sqrt{D\tau} \quad \text{Einstein relation: } \frac{D}{\mu} = \frac{kT}{q}$$

$$I = I_0 \cdot \left[\exp \left(\frac{V}{\eta kT} \right) - 1 \right]$$

$$\text{Equilibrium: } V_0 = \frac{kT}{q} \ln \frac{p_p}{p_n} = \frac{kT}{q} \ln \frac{N_a}{n_i^2 / N_d} = \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2}$$